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(71) Applicant: **MICRON TECHNOLOGIES, INC.**
[US/US]; 8000 S. Federal Way, Boise, ID 83707-0006
(US).

(72) Inventor: **BAKER, R., Jacob**; 5501 S. Linder Road,
Meridian, ID 83642 (US).

(74) Agent: **D'AMICO, Thomas, J.**; Dickstein Shapiro Morin
& Oshinsky LLP, 2101 L Street NW, Washington, DC
20037-1526 (US).

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